

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	8105	(mems micro\$1electro\$1mechanical) and data near2 stor\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/09 18:19
L2	727	1 and (cars atomic adj resolution adj storage)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/09 18:26
L3	656	2 and (mov\$3 displac\$5 deflect\$4 micro\$1mover)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/09 18:20
L4	577	3 not (@rlad>"20040419" @ad>"20040419")	US-PGPUB; USPAT; EPO; JPO	OR	OFF	2005/12/09 18:21
L5	1	4 and (mov\$3 displac\$5 deflect\$4 micro\$1mover) same (selective\$2 align\$4) with (polymer\$2 thermoplastic thermoset pmma epoxy photoresist resist composition coat\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/09 17:53
L6	0	4 and (mov\$3 displac\$5 deflect\$4 micro\$1mover) same (pattern\$3 etch\$3) with (polymer\$2 thermoplastic thermoset pmma epoxy photoresist resist composition coat\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/09 17:54
L7	73	4 and (mov\$3 displac\$5 deflect\$4 micro\$1mover) same (polymer\$2 thermoplastic thermoset pmma epoxy photoresist resist composition coat\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/09 17:54
L8	73	7 and (polymer\$2 thermoplastic thermoset pmma epoxy photoresist resist composition coat\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/09 18:23
L9	91	4 and (method process manufactur\$3 fabricat\$3) near5 (mems micro\$1electro\$1mechanical)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/09 18:20
L10	55	9 not 8	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/09 18:10

L12	10244	(method process manufactur\$3 fabricat\$3) near5 (mems micro\$1electro\$1mechanical)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/09 18:20
L13	7508	12 not (@rlad>"20040419" @ad>"20040419")	US-PGPUB; USPAT; EPO; JPO	OR	OFF	2005/12/09 18:21
L14	8466	12 not (@rlad>"20040419" @ad>"20040419")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/12/09 18:22
L15	5763	14 and (mov\$3 displac\$5 deflect\$4 micro\$1mover)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/09 18:22
L16	4026	15 and (polymer\$2 thermoplastic thermoset pmma epoxy photoresist resist composition coat\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/09 18:23
L17	733	16 and (polymer\$2 thermoplastic thermoset pmma epoxy photoresist resist composition coat\$3) with (selective\$2 align\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/09 18:25
L18	596	17 and (polymer\$2 thermoplastic thermoset pmma epoxy photoresist resist composition coat\$3) with (pattern\$3 etch\$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/09 18:25
L19	16	18 and (cars atomic adj resolution adj storage)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/12/09 18:26